**Progress** 

Course outline

Week 1 - Basics of

casting process

Manufacturing Processes

Week 2 - Introduction to

Rate of solidification

Week 4 - Estimation of solidification time with

Week 5 - Machining

Week 6 - Cutting tool life

Week 7 - Introduction to

Micro-Systems Fabrication

 Introduction to Advanced Machining Processes

Classification of Machining

Micro Fabrication Technology

Introduction to Wet Etching

Introduction to Dry Etching

O Quiz: Assignment 7

Assignment 7 solution

Manufacturing Process

Week 8 - Abrasive water jet machining and Ultrasonic

Week 9 - Introduction to Electrochemical Machining

**Machining Process** 

Week 10 - Electro-discharge

Week 11 - Laser Beam and Electron Beam Machining

Week 12 - Metal Forming

Technology I and II: Feedback

Week 3 - Gating Systems and

different conditions and Riser

course work?

Week 0

design

Processes

estimation

Technology

Processes

 Silicon growth & Crystallography

Photolithography

Soft Lithography

Techniques

Techniques

For Week 07

Machining

Processes

Processes

**Text Transcripts** 

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No, the answer is incorrect.

Accepted Answers: All of the above.

Score: 0

How does an NPTEL online





Announcements

**About the Course** 

Ask a Question

Mentor

## Unit 9 - Week 7 - Introduction to Micro-Systems Fabrication Technology

Assignment 7  The due date for submitting this assignment has passed.  As per our records you have not submitted this assignment.	Due on 2020-03-18, 23:5	59 IST.
Assignment 7		
Precision machining caters what limit of machining accuracy?		1 poir
○ 1-10 µm		
Ο 0.1-1 μm		
○ 10-100 µm ○ 1-10 nm		
No, the answer is incorrect.		
Score: 0 Accepted Answers:		
0.1-1 µm		
Ion beam machining can produce a minimum machining accuracy up to?		1 poin
○ 0.1 nm		
Ο 1 μm		
○ 1 nm ○ 100 μm		
No, the answer is incorrect.		
Score: 0 Accepted Answers:		
1 nm		
3) Which of the following mechanical abrasion process utilizes loose abrasives?		1 poin
OHoning		
Grinding		
Sawing Buffing		
No, the answer is incorrect.		
Score: 0 Accepted Answers:		
Buffing		
4) Which of the following device is used in AFM?		1 poin
○ Electronic IC		
Cantilever tip		
DMD mirrors     Smoothened silicon substrate		
No, the answer is incorrect.		
Score: 0 Accepted Answers:		
Cantilever tip		
5) Surface micromachining is:		1 poin
Additive process		
Subtractive process		
Constant volume process		
None of the above.  No, the answer is incorrect.		
Score: 0		
Accepted Answers: Additive process		
6) Physical dry etching utilize which of the following etchant material?		1 poin
Etchant gases		
Etchant powders		
Olons, electrons or photons		
All of the above.		
No, the answer is incorrect. Score: 0		
Accepted Answers: lons, electrons or photons		
7) Which of the following photoresist presents the feature of dissolving away when directly exposed	by the UV light?	1 poin
Negative photoresist		
O Positive photoresist		
None of the above shows such characteristics.		
All the photoresists present such behavior.		
No, the answer is incorrect. Score: 0		
Accepted Answers: Positive photoresist		
8) The resolution, b of lithography, is given by the formula, where λ and s are wavelength and o	distance between mask and	1 poin
notoresist layer, respectively.		
○ b=0.5λs		
b=0.5 (λs)^1.5		
○ b=1.5λs ○ b=1.5 (λs)^0.5		
No, the answer is incorrect.		
Score: 0 Accepted Answers:		
$b=1.5 (\lambda s)^{0.5}$		
9) SU8, negative tone photoresist does not contain which of the following compound?		1 poin
○ Epoxy resin		
Cyclopentanone solvent		
Cyclopentanone solvent     Photoacid generator		
No, the answer is incorrect.		
Score: 0 Accepted Answers:		
Curing agent		
40) Miliah of the following schools is not send for a set to a line in the set of the se		1 poin
10) which of the following scheme is not used for a water-level bonding scheme?		
Which of the following scheme is not used for a wafer-level bonding scheme?      Field assisted bonding		